

ABSTRACT

A method and device for determining projection lens pupil transmission distribution in a photolithographic imaging system, the device including an illumination source; a transmissive reticle; an aperture layer having an illumination source side and a light emission side and comprising a plurality of openings therethrough; a diffuser mounted on the illumination source side of the aperture layer; a projection lens system; and an image plane, in which a pupil image corresponding to each of the plurality of openings in the aperture layer is formed at the image plane when radiation from the illumination source passes through the reticle, the diffuser, the aperture layer and the projection lens system, the pupil image having a projection lens pupil transmission distribution.